

Title (en)

EXPOSURE DEVICE FOR THE STRUCTURED EXPOSURE OF A SURFACE

Title (de)

BELICHTUNGSEINRICHTUNG ZUR STRUKTURIERTEN BELICHTUNG EINER FLÄCHE

Title (fr)

DISPOSITIF D'ÉCLAIRAGE POUR L'ÉCLAIRAGE STRUCTURÉ D'UNE SURFACE

Publication

**EP 2695015 A1 20140212 (DE)**

Application

**EP 12722065 A 20120308**

Priority

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Abstract (en)

[origin: WO2012136199A1] The invention relates to an exposure device (14) for the structured exposure of a wafer, comprising at least one exposure arrangement (13) with which a beam (2) that is separated into two sub-beams (2.1, 2.2) is modulated via two micromirror arrays (5.1; 5.2) in order to increase the throughput speed during the exposure of wafers.

IPC 8 full level

**G02B 26/08** (2006.01); **G03F 7/20** (2006.01)

CPC (source: EP KR US)

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Citation (search report)

See references of WO 2012136199A1

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